

FIG. la

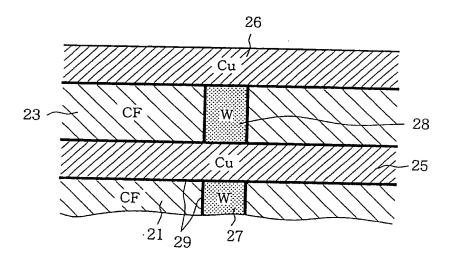
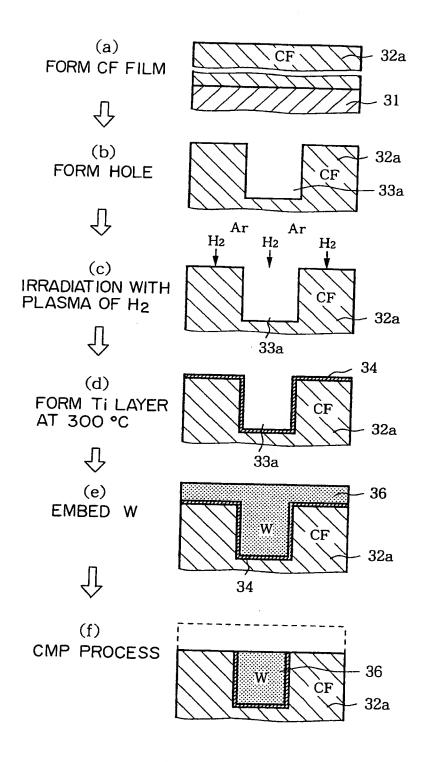
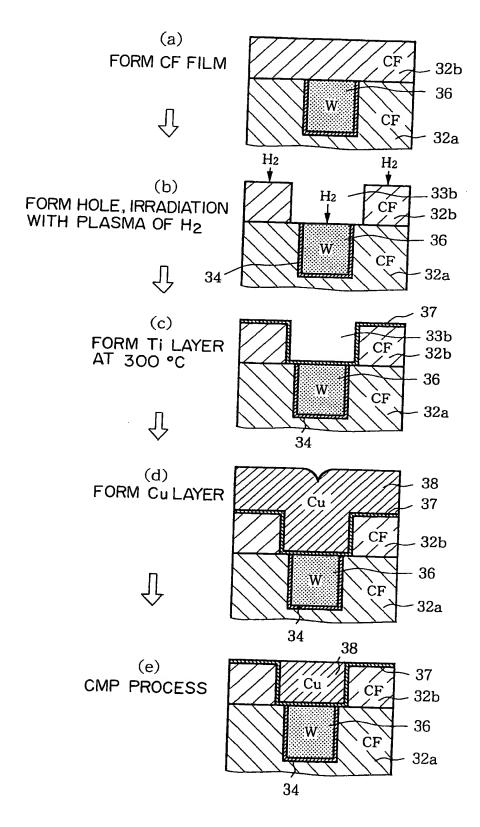


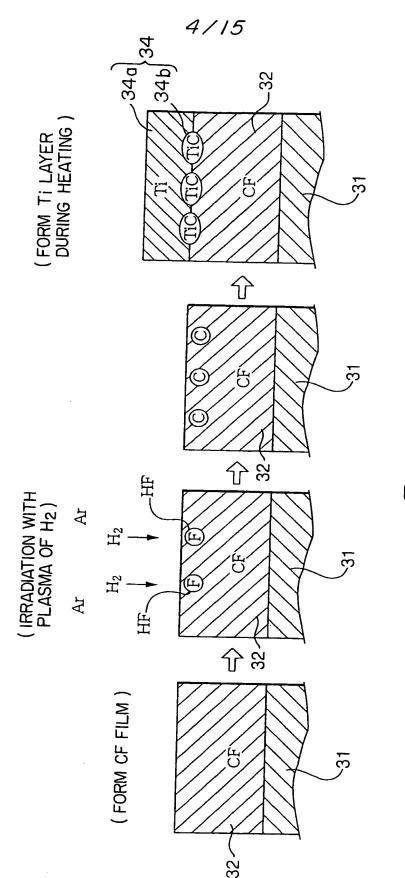
FIG. 1b



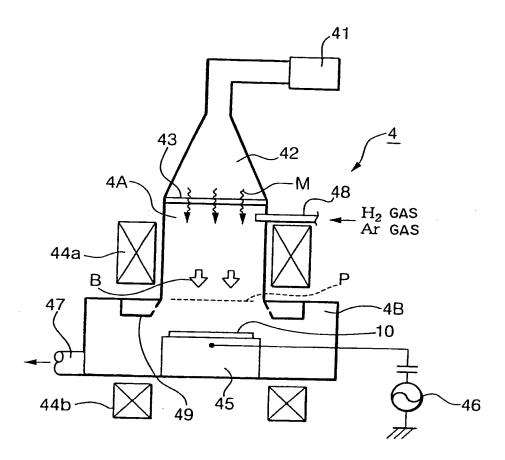
F1G. 2



F1G. 3



F 1 G. 4



F I G. 5

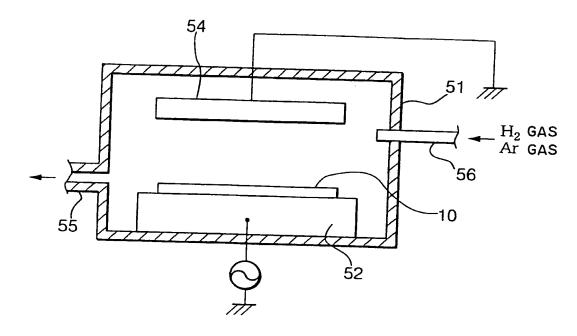
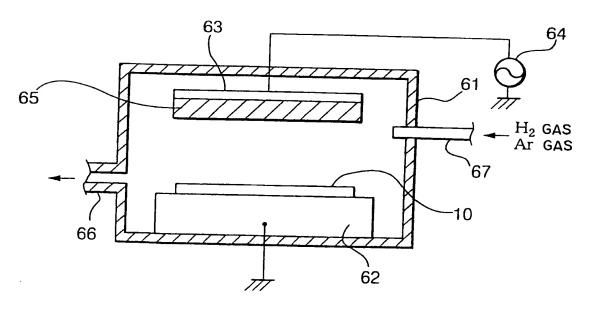


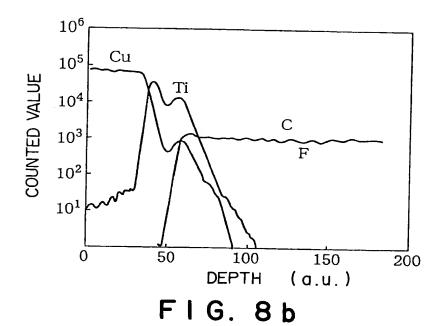
FIG. 6



F I G. 7

Cu	2000Å			
Ti	500Å			
CF 5000Å				
Si				

F1G. 8a



 10^{6} Cu 10⁵ COUNTED VALUE 10⁴ С 10³ F 10² Si 10¹ 0 100 DEPTH 150 (a.u.) 50 200

F I G. 8c

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Cu	2000Å				
Ti	500Å				
SiO ₂ 5000Å					
Si					

FIG. 9a

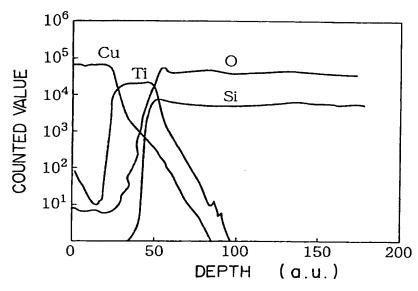


FIG. 9b

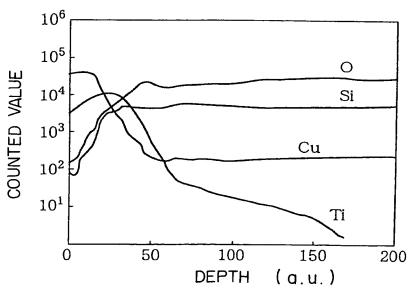
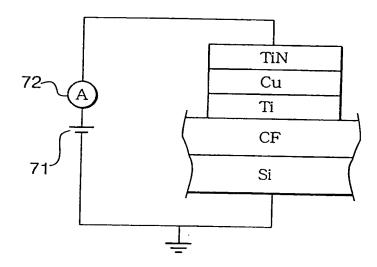


FIG. 9c



F I G. 10

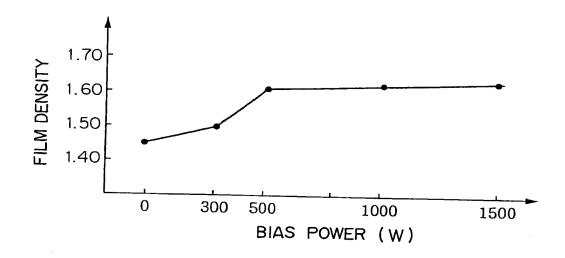
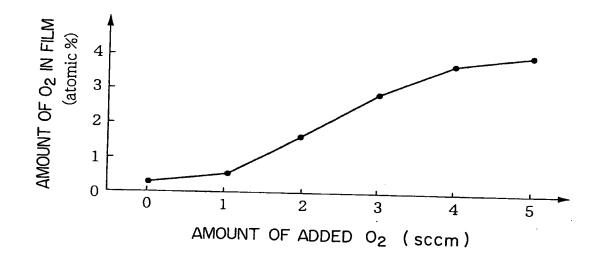


FIG. IIa

BIAS POWER (W)	0	300	500	1000	1500
MTTF (hr)	0.98	1.63	1.65	1.80	1.92

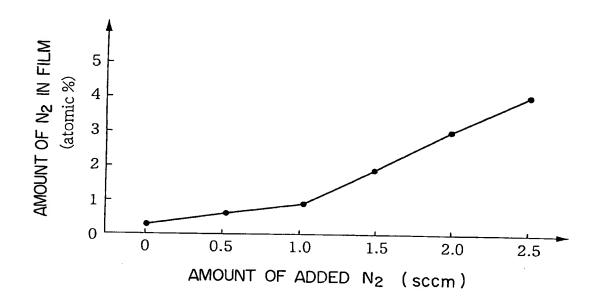
FIG. IIb



F I G. 12 a

AMOUNT OF ADDED O2 (sccm)	0	1	2	3	4	5
MTTF (hr)	1.92	2.13	2.11	1.90	0.84	0.65

FIG. 12b



F I G. 13a

AMOUNT OF ADDED N2 (sccm)	0	0.5	1.0	1.5	2.0	2.5
MTTF (hr)	1.92	1.81	1.70	1.65	1.55	0.78

F I G. 13b

AMOUNT OF ADDED BF3 (sccm)	AMOUNT OF B IN FILM
0.1	5×10 ⁻⁴ atomic %
0.2	10 ⁻³ atomic %
1	0.01 atomic %
5	0.1 atomic %
10	1 atomic %
20	2 atomic %

F I G. 14 a

AMOUNT OF ADDED BF3 (sccm)	0.1	0.2	1	5	10	20
MTTF (hr)	1.98	2.35	2.65	2.68	2.76	0.75

F I G. 14 b

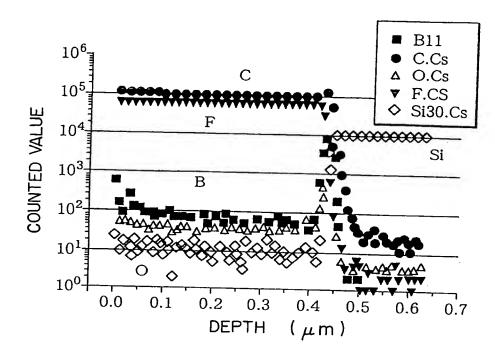
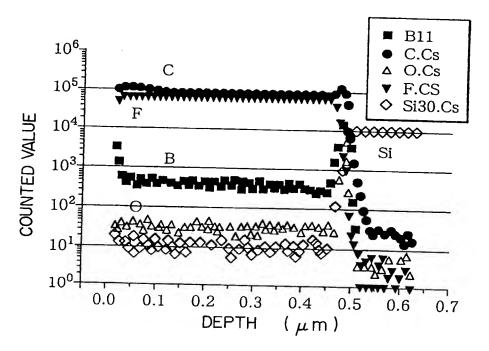
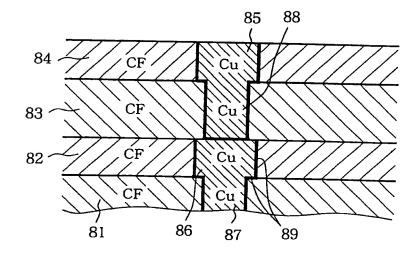


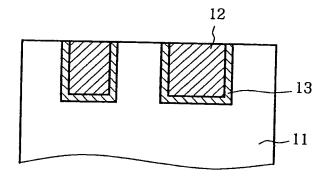
FIG. 15a



F I G. 15 b



F I G. 16



F I G. 17